

Supporting Information

Improved Photoelectrochemical Hydrogen Gas Generation on Sb₂S₃ Films Modified with an Earth-Abundant MoS_x Co- Catalyst

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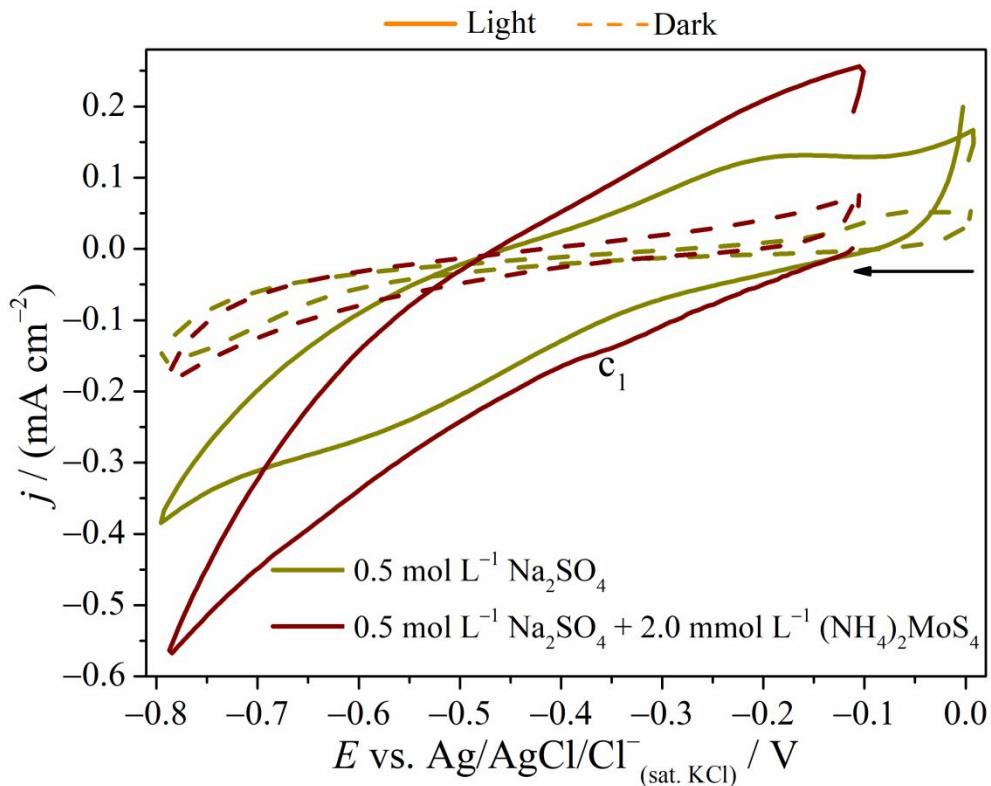


Figure S1. Cyclic voltammograms at a scan rate of 20 mV s⁻¹ in the dark and under solar light simulator (AM1.5G and 100 mW cm⁻²) for PT-Sb₂S₃ film in 0.5 mol L⁻¹ Na₂SO₄ pH 5 and 0.5 mol L⁻¹ Na₂SO₄ + 2.0 mmol L⁻¹ (NH₄)₂MoS₄ pH 5.

According to Figure S1, the voltammogram obtained under illumination for PT-Sb₂S₃ film in 0.5 mol L⁻¹ Na₂SO₄ + 2.0 mmol L⁻¹ (NH₄)₂MoS₄ displayed a shoulder cathodic peak c_1 at ca. -0.35 V. Since this peak was not observed in the voltammogram under illumination for PT-Sb₂S₃ film in only 0.5 mol L⁻¹ Na₂SO₄, the shoulder peak c_1

was assigned to the PEC reduction of $[\text{MoS}_4]^{2-}$ as shown in Equation 1 in the manuscript.

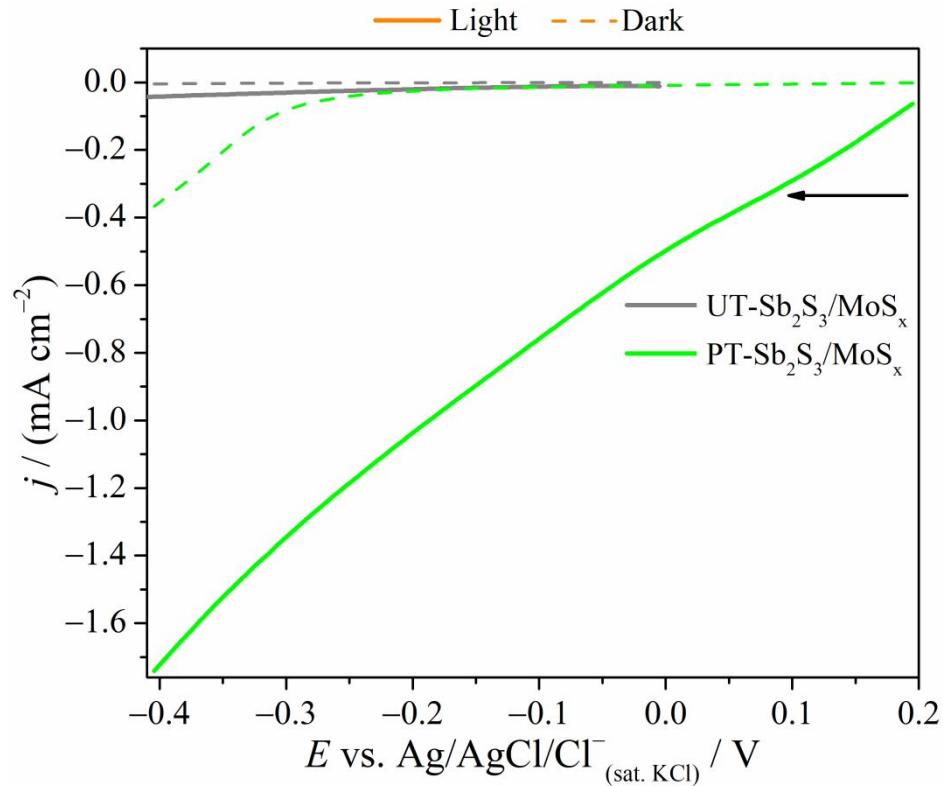


Figure S2. Linear sweep voltammograms at a scan rate of 50 mV s⁻¹ in the dark and under solar light simulator (AM1.5G and 100 mW cm⁻²) for UT-Sb₂S₃/MoS_x and PT-Sb₂S₃/MoS_x films. The electrolyte was an N₂-saturated solution of 1.0 mol L⁻¹ H₂SO₄ at pH 0.6. The MoS_x was photoelectrodeposited on the UT-Sb₂S₃ and PT-Sb₂S₃ films for 10 min.

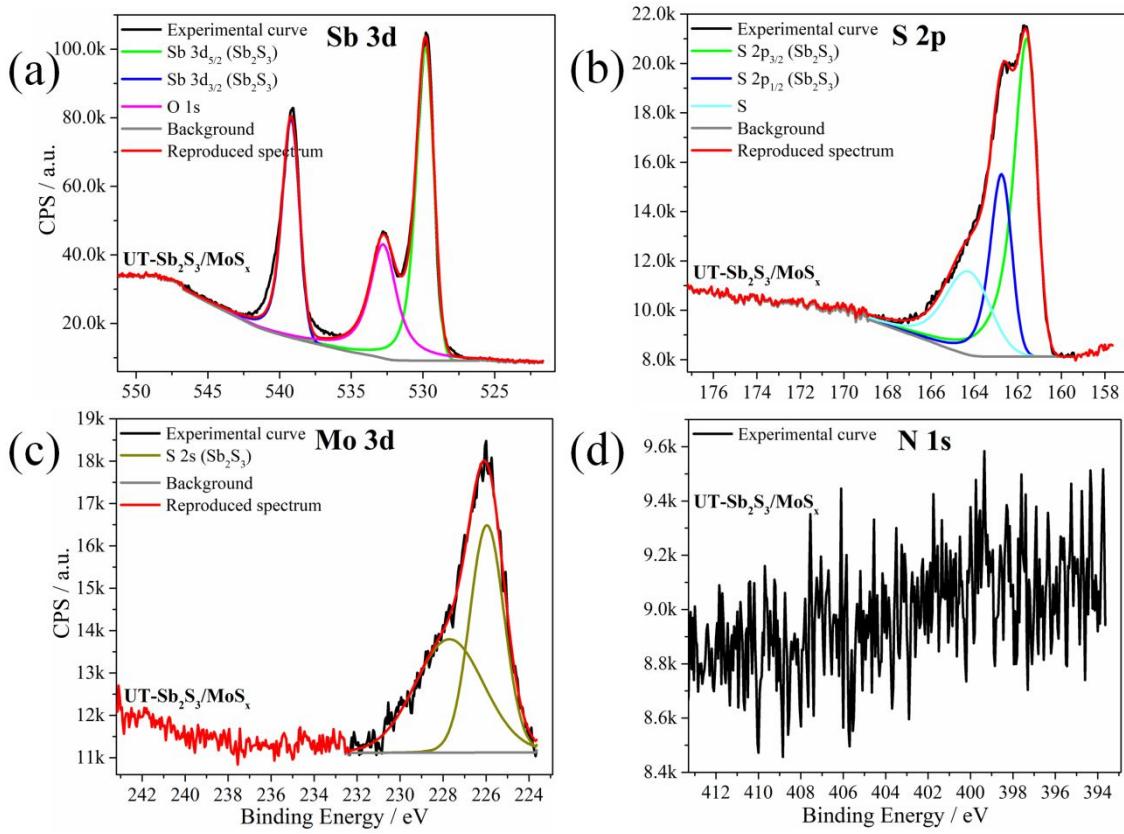


Figure S3. High-resolution XPS spectra of (a) Sb 3d, (b) S 2p, (c) Mo 3d, and (d) N 1s

core levels for UT-Sb₂S₃/MoS_x film. The MoS_x was photoelectrodeposited on the UT-Sb₂S₃ film for 10 min.

From Figure S3a, the Sb 3d spectrum for the UT-Sb₂S₃/MoS_x film presented photoemission peaks at 529.6 (Sb 3d_{5/2}) and 539.0 eV (Sb 3d_{3/2}), which are assigned to Sb³⁺ in Sb₂S₃.¹ Additionally, the spectrum displayed a photoemission peak at 532.8 eV

(O 1s) and that is probably associated with adsorbed water.² The S 2p spectrum for the UT-Sb₂S_x/MoS_x film (cf. Figure S3b) displayed photoemission peaks at 161.4 (S 2p_{3/2}) and 162.6 eV (S 2p_{1/2}) which are characteristic for S²⁻ in Sb₂S₃.³ The additional peak at 163.9 eV is probably attributed to residual elemental sulphur⁴ on the Sb₂S₃ films' surface and this may have come from the sulphurisation step. For the Mo 3d spectrum in Figure S3c, one can observe the photoemission peaks at 226.0 and 227.7 eV for S 2s,⁵ which are possibly assigned to Sb₂S₃. The N 1s spectrum (see Figure S3d) did not display any photoemission signal. This result was already expected for the UT-Sb₂S_x/MoS_x film since the Sb₂S₃ film was not subjected to N₂ plasma treatment. We only observed photoemission peak in the N 1s region for the Sb₂S₃ films once treated under N₂ plasma, for more details the reader is referred to our latest work⁶ and the discussion of Figure 4 in this manuscript.

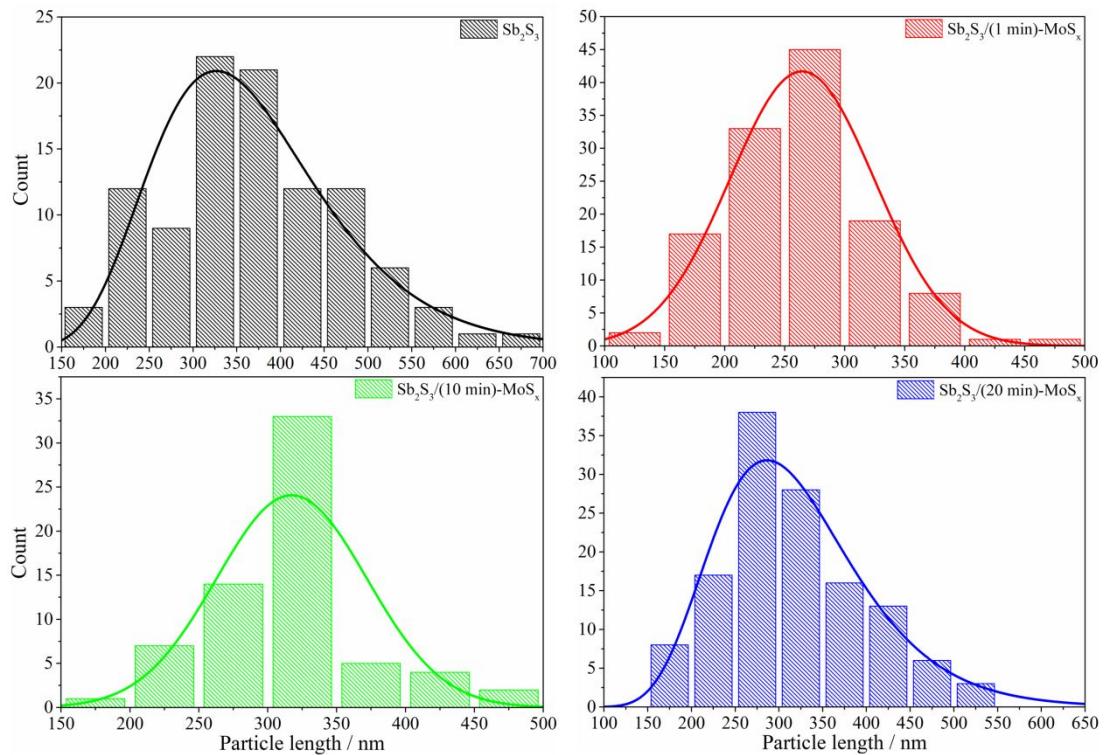


Figure S4. Particle size distribution histograms for PT-Sb₂S₃ and PT-Sb₂S₃/(1, 10, or 20 min)-MoS_x films.

To obtain the particle size distribution, histograms were constructed and are displayed in Figure S4. We employed the ImageJ^{7,8} (version 1.51j8) software to measure the length of up to 130 particles from the SEM micrographs. According to Figure S4, the estimated particle length for bare PT-Sb₂S₃ film was 325 nm, whilst the particle length for PT-Sb₂S₃ films superficially modified with MoS_x photoelectrodeposited for 1, 10, and 20 min was ca. 275, 325, and 275 nm, respectively.

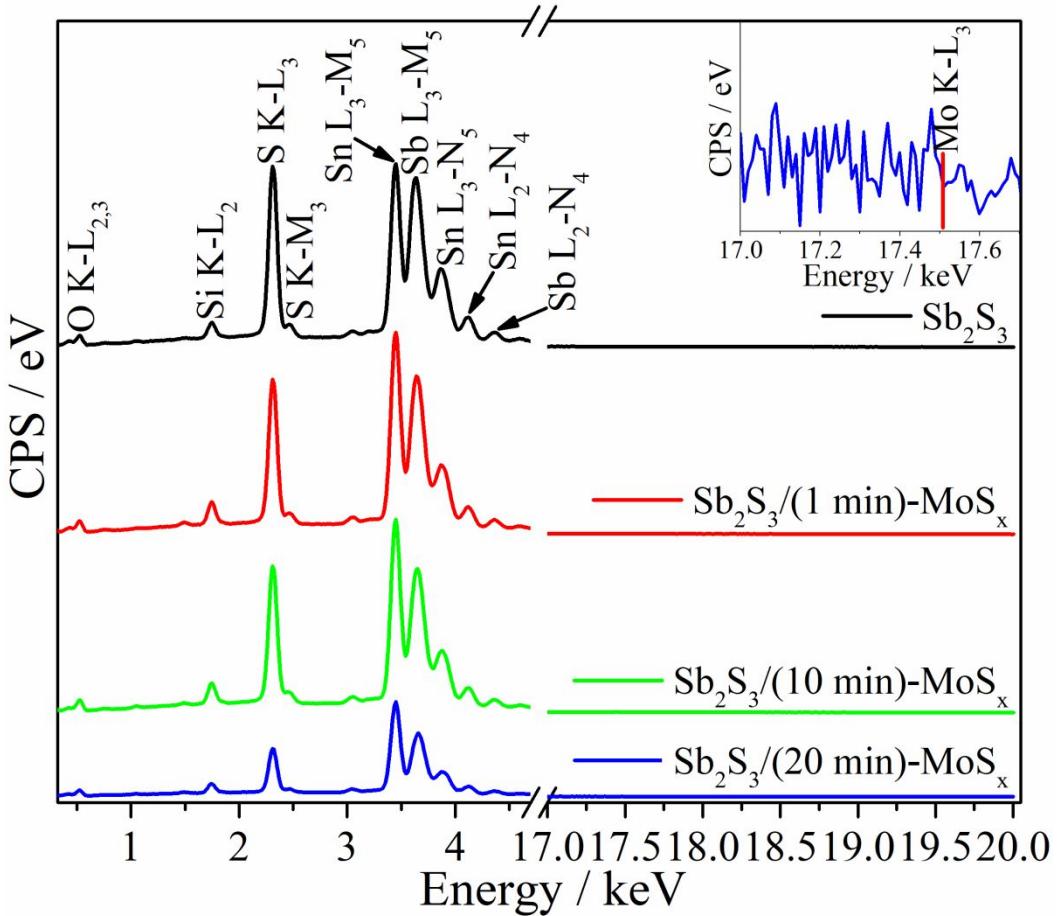


Figure S5. EDS spectra for PT-Sb₂S₃ and PT-Sb₂S₃/(1, 10, or 20 min)-MoS_x films. The characteristic X-ray emission lines energies of the elements were assigned using Grieken and Markowicz's database.⁹ The peaks assigned to the O, Si, and Sn elements are from the substrate (glass/FTO).

Table S1. Atomic percentage of Sb and S obtained from the EDS spectra for PT-Sb₂S₃ and PT-Sb₂S₃/(1, 10, or 20 min)-MoS_x films.

Sample	Atomic percentage / %		Atomic ratio S/Sb
	Sb	S	
Sb_2S_3	21	34	1.6
$\text{Sb}_2\text{S}_3/(1 \text{ min})\text{-MoS}_x$	17	30	1.8
$\text{Sb}_2\text{S}_3/(10 \text{ min})\text{-MoS}_x$	15	29	1.9
$\text{Sb}_2\text{S}_3/(20 \text{ min})\text{-MoS}_x$	12	23	1.9

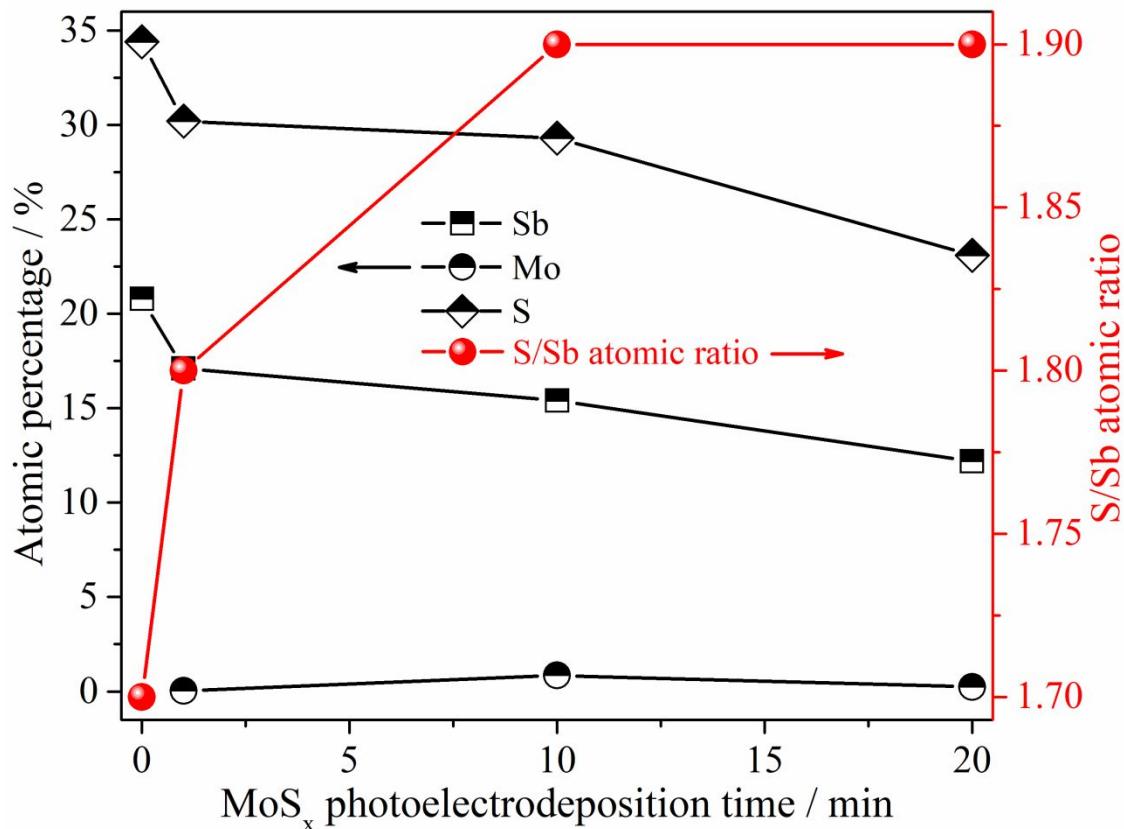


Figure S6. Atomic percentage of Sb, Mo and S, and S/Sb atomic ratio obtained from the EDS spectra for PT-Sb₂S₃ and PT-Sb₂S₃/(1, 10, or 20 min)-MoS_x films.

Table S2. Binding energy assignment from the high-resolution XPS spectra for PT-Sb₂S₃ and PT-Sb₂S₃/(1 or 10 min)-MoS_x films.

Core level		Binding energy / eV				
		PT-	PT-Sb ₂ S ₃ /(1 min)-	PT-Sb ₂ S ₃ /(10 min)-	Assignment	Ref.
		Sb ₂ S ₃	MoS _x	MoS _x		
Sb 3d	Sb 3d _{3/2}	540.4	539.9	539.2	Sb ₂ S ₃	10,11
	Sb 3d _{5/2}	531.0	530.5	529.8	Sb ₂ S ₃	10,11
	O 1s	532.1	532.2	531.9	Adsorbed O ₂ , H ₂ O, etc.	12
Mo 3d	Mo 3d _{3/2}	-	232.9	233.2	MoS ₂	13–15
		-	236.3	236.2	MoO ₃ and/or MoO _x O _y	14,16–18
	Mo 3d _{5/2}	-	229.8	230.0	MoS ₂	13–15
Mo 3d	Mo 3d	-	233.2	233.0	MoO ₃ and/or MoO _x O _y	14,16–18
	S 2s	232.8	-	-	S-N bond	19–21
		-	226.1	226.6	MoS ₂	14
S 2p	S 2p	168.5	-	-	S-N bond	19,20,22
		169.5	-	-	S-N bond	19,20,22
	S 2p _{3/2}	-	161.4	161.8	S ²⁻ in MoS _x	23,24
S 2p	-	162.6	163.1	S ₂ ²⁻ in MoS _x	23,24	
	S 2p _{1/2}	-	162.4	162.8	S ²⁻ in MoS _x	23,24
		-	163.6	164.1	S ₂ ²⁻ in MoS _x	23,24
N 1s	N 1s	401.7	399.5	398.9	S-N bond	20,21,25
	Mo 3p _{3/2}	-	395.8	396.1	MoS ₂	14

Table S3. Percentage error values for each circuit element to fit the complex-plane impedance diagrams obtained at -0.2 V vs. Ag/AgCl/Cl⁻_(sat. KCl) and under solar light simulator (AM1.5G and 100 mW cm⁻²) for PT-Sb₂S₃ and PT-Sb₂S₃/(1 min)-MoS_x films. The electrolyte was an N₂-saturated solution of 1.0 mol L⁻¹ H₂SO₄ at pH 0.6.

Circuit element	Percentage error ^a / %	
	PT-Sb ₂ S ₃	PT-Sb ₂ S ₃ /(1 min)-MoS _x
R_s	0.95	0.60
$R_{ct,sc}$	11	8.9
$R_{ct,d}$	5.4	5.2
Q_{sc}	6.8	3.8
$\alpha_{f,sc}$	5.7	1.4
Q_d	2.1	9.8
$\alpha_{f,d}$	0.32	0.70

^aThe fit of the complex-plane impedance diagrams for PT-Sb₂S₃ and PT-Sb₂S₃/(1 min)-MoS_x films delivered chi-squared (χ^2) values of 0.00048296 and 0.00022833, respectively.

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